

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant :	Lawrence D. Wong	Art Unit :	2826
Serial No. :	10/802,331	Examiner :	Scott Wilson
Filed :	March 16, 2004	Conf. No. :	3745
Title :	ELECTRON-BEAM TREATED CDO FILMS		

MAIL STOP AMENDMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Applicants request consideration of the references listed on the attached PTO-1449 form. Under 35 USC §120, this application relies on the earlier filing date of application serial number 10/161,104, filed on May 30, 2002. The following references were submitted to and/or cited by the Office in the prior application and, therefore, are not provided in this application.

This statement is being filed after a first Office action on the merits, but before receipt of a final Office action or a Notice of Allowance. Please apply the \$180 late submission fee of §1.17(p) and any other charges or credits to Deposit Account No. 06-1050 referencing Attorney Docket Number 10559-586002.

Respectfully submitted,

Date: _____

April 27, 2007



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Substitute Form PTO-1448 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 10559-586002	Application No. 10/802,331
Information Disclosure Statement by Applicant (Use several sheets if necessary)		Applicant Lawrence D. Wong	
		Filing Date March 16, 2004	Group Art Unit 2826
(37 CFR §1.98(b))			

U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	AA	4,848,141	07-1989	Oliver et al.	73	81	
	AB	6,340,628	01-2002	Van Cleemput et al.	438	586	
	AC						
	AD						

Foreign Patent Documents or Published Foreign Patent Applications							
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation Yes No
	AE						
	AF						
	AG						

Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
	AH	Hara et al., "Mechanism of Mechanical and Chemical Polishing in Low Dielectric Constant Plasma-Enhanced Chemical Vapor Deposition SiOC Layer from hexamethyldisiloxane", Electrochem. And Solid State Lett., 4(8):65-67 (Aug. 2001).
	AI	Music et al., "Synthesis and Mechanical Properties of Boron Suboxide Thin Films", J. Vac. Sci. Technol. A, 20(2):335-337 (Apr. 2002).
	AJ	Liu, P.T. et al., "The Effects of Plasma Treatment for Low Dielectric Constant Hydrogen Silsesquioxane (HSQ)", Thin Solid Films v. 332, pgs. 345-350 (1998).
	AK	Kondoh, E., "Structural Change in Porous Silica Thin Film after Plasma Treatment", Electrochem. and Solid-State Lett., 1(5):224-226 (1998).
	AL	Gidley et al., "Determination of pore-Size Distribution in Low-Dielectric Thin Films", App. Phys. Lett., 76(10):1282-1284 (2000).
	AM	Loboda et al., "Using Trimethylsilane to Improve Safety, Throughput and Versatility in PECVD Processes", Electrochem. Proc., 97(10):443-453.
	AN	Loboda et al., "Deposition of Low-K Dielectric Films Using Trimethylsilane", Proc. Of the Symposia on Electrochem. Proc. In ULSI Fabrication and Interconnect and Contact Metallization: Materials, Processes and Reliability, pgs. 145-152 (1998).
	AO	Sagahara et al., "Low Dielectric Constant Carbon Containing SiO ₂ Films Deposited by PECVD Techniques Using a Novel CVD Precursor", Int'l. Dielectrics for ULSI Multilevel Interconnection Conference, pgs. 19-25 (1997).
	AP	Kanaya et al., "Penetration and Energy-Loss Theory of Electrons in Solid Targets", J. Phys. D.: Appl. Phys., vol. 5, pgs. 43-58 (1972).

Examiner Signature	Date Considered
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	